

TARGETS WITH HIGH PASS-THROUGH-FLUX MAGNETIC MATERIAL  
SPUTTERING, METHOD OF MANUFACTURE AND HARD DISK  
OBTAINABLE THEREOF

A target for a deposition apparatus is formed by blending at least two different types of powders together and consolidating the powders with a powder metallurgy process to form a billet. The target is then formed from the billet. The target includes a first material phase having a first PTF and a second material phase having a second PTF higher than the first PTF. The second PTF is also higher than a PTF of a material having the same chemistry as the target.

(no figure)



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